IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: LEE, Jin Gyu et al Conf.:

Appl. No.: NEW Group:

Filed: October 16, 2003 Examiner:

For: SILOXANE-BASED RESIN AND METHOD OF

FORMING AN INSULATING FILM BETWEEN INTERCONNECT LAYERS OF A SEMICONDUCTOR

DEVICE USING THE SAME

PRELIMINARY AMENDMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

October 16, 2003

Sir:

The following preliminary amendments and remarks are respectfully submitted in connection with the above-identified application.

This amendment includes:

Amendments to the Specification

Remarks